

Scatterometry For Lithography Process Control And Characterization In IC Manufacturing By Yiorgos Kostoulas

By Yiorgos Kostoulas

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Determination of lithography process control -

Abstract Spectroscopic Scatterometry was employed for definition of control metrics for lithography process tool optimization. Normal incidence unpolarized

<http://adsabs.harvard.edu/abs/2003SPIE.5038.1168M>

New approaches for scatterometry-based metrology -

for critical distance and overlay measurement and process control. Scatterometry; Process control; metrology solution for lithography process control of

<http://nanolithography.spiedigitallibrary.org/article.aspx?articleid=1166700&journalid=95>

Next Generation Lithography - ASML -

Next Generation Lithography scatterometry for more process robust metrology Litho patterning process control for CD and Overlay

http://www.asml.com/doclib/investor/presentations/2008/asml_20080523_Confab_MvdB_FINAL.pdf

Real time scatterometry: a new metrology for in -

Real time scatterometry: a new metrology for in situ microelectronics process control
Mohamed El Kodadi, especially for the lithography and plasma

https://hal.archives-ouvertes.fr/docs/00/46/22/57/PDF/PESM_abstract.pdf

RISS - -

Application of atomic force microscopy to lithography characterization and control SPIE
process SPIE Specular spectroscopic scatterometry in DUV lithography

http://m.riss.kr/search/detail/DetailViewOtherContents.do?p_mat_type=e21c2016a7c3498b&control_no=2e1cb0d8395a5660ffe0bdc3ef48d419

In situ real time process characterization in -

Abstract. To optimize nanoimprint lithography(NIL), it is essential to be able to
characterize and control the NIL process in situ and in real time.

<http://scitation.aip.org/content/aip/journal/apl/85/18/10.1063/1.1811396>

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Patent US7382447 - Method for determining -

2002 and entitled SPECTROSCOPIC CD METROLOGY FOR SUB-100 nm
LITHOGRAPHY PROCESS CONTROL. via a lithography system. The scatterometry
Patents - Send

<http://www.google.com/patents/US7382447>

Novel implementations of scatterometry for -

Metrology, Inspection, and Process Control for Microlithography XVI; Daniel J. C. Herr;
Santa Clara, CA | March 03, 2002

<http://proceedings.spiedigitallibrary.org/proceeding.aspx?articleid=881200>

Kostoulas - Bilder, News, Infos aus dem Web -

Konstantinos Heike Kostoulas

<http://www.vebidoo.de/kostoulas>

SPIE | Optical Engineering | Scatterometry of -

Jo rg W. Baumgart and Horst Truckenbrodt "Scatterometry of honed surfaces", Opt
Optical scatterometry evaluation of groove depth Lithographic Process Control;

<http://opticalengineering.spiedigitallibrary.org/article.aspx?articleid=1075318>

Patent US6987572 - Methods and systems for -

Methods and systems for evaluating and controlling a lithography process are provided. For example,

<http://www.google.com/patents/US6987572>

CiteSeerX FIRST PRINCIPLE-BASED STATE ESTIMATOR -

This lithography process simulator is used to create a The major obstacle to implementing scatterometry in a process control setting is profile inversion

<http://citeseerx.ist.psu.edu/viewdoc/summary?doi=10.1.1.134.9941>

Progress in Semiconductor Materials for -

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LOW CONCENTRATION NITRIDE ALLOYS I

<https://www.kinokuniya.co.jp/f/dsg-02-9781558996281>

Scatterometry solutions and vision for advanced -

Date Published: 5 April 2007 PDF: 11 pages Proc. SPIE 6518, Metrology, Inspection, and Process Control for Microlithography XXI, 651855 (5 April 2007); doi: 10.1117

<http://spie.org/Publications/Proceedings/Paper/10.1117/12.728716>

Patent US20020072003 - Process control for micro- -

to thereby enable the process control. A method is presented for controlling a process to be applied to a patterned structure in a production run.

<http://www.google.co.za/patents/US20020072003>

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Towards traceability in scatterometric -optical -

Towards traceability in scatterometric Bernd Bodermann, mensional metrology f or optical lithography is li ited to relative measurements for process control

http://www.dgao-proceedings.de/download/113/113_a28.pdf

Progress in semiconductor materials for -

Preface: Materials Research Society Symposium Proceedings: Low Concentration Nitride Alloys I: Luminescent Characteristics of InGaAsP/InP Multiple Quantum Well
<http://topics.libra.titech.ac.jp/recordID/catalog.bib/BA5883712X>

Scatterometry for EUV lithography at the 22-nm -

Scatterometry for EUV lithography at the metrology for EUV lithography process control. explore scatterometry's application to a typical
http://www.academia.edu/8172174/Scatterometry_for_EUV_lithography_at_the_22-nm_node

Simultaneous measurement of optical properties and -

et al. "Simultaneous measurement of optical properties and geometry of resist using multiple scatterometry targets", Lithography process control using
<http://nanolithography.spiedigitallibrary.org/article.aspx?articleid=1099845>

Metrology, Inspection, and Process Control for -

SPIE Advanced Lithography; Publications. Conference Proceedings; SPIE Digital and Process Control for Microlithography XIII. Editor(s): Bhanwar Singh. Format
<http://spie.org/Publications/Proceedings/Volume/3677>

A Simulation Framework For Lithography Process -

11/14/2001 1 A Simulation Framework For Lithography Process Monitor & Control Using Scatterometry SFR Workshop Nov. 14, 2001 Junwei Bao, Paul Friedberg, Prof. Costas
http://impact.ee.ucla.edu/archive/secure/archives/workshops/2001_nov/poster/SFR_poster_Litho_Bao.pdf

Lithographic Process Control - SPIE Digital -

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<http://spiedigitallibrary.org/collection.aspx?categoryid=6206>

Advanced lithography parameters extraction by -

Advanced lithography parameters extraction by using scatterometry system Metrology, inspection, and process control for microlithography XXI :
<http://cat.inist.fr/?aModele=afficheN&cpsidt=19224948>

Holistic lithography for EUV: NXE: 3100 -

printed wafers using an advanced scanner model and scatterometry lithography, wafer lithography and process advanced lithography control",

<http://www.brion.com/wordpress/wp-content/uploads/2010/08/Holistic-lithography-for-EUV.pdf>

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http://ieeexplore.ieee.org/xpl/abstractKeywords.jsp?reload=true&arnumber=1134163&sortType%3Dasc_p_Sequence%26filter%3DAND%28p_Publication_Number%3A66%29%26pageNumber%3D23%26rowsPerPage%3D75

Manufacturing implementation of scatterometry and -

Manufacturing implementation of scatterometry and other techniques for Metrology, inspection, and process control for Lithography; Optical control;

<http://cat.inist.fr/?aModele=afficheN&cpsidt=21919079>

Defense Technical Information Center Compilation -

Defense Technical Information Center Compilation Process Control and Characterization in IC in IC Manufacturing Yiorgos Kostoulas*,

<http://www.dtic.mil/dtic/tr/fulltext/u2/p012609.pdf>

Integrated ODP Metrology Matching To Reference -

Advanced DRAM manufacturing demands rigorous and tight process control using integrated scatterometry based control For Lithography Process Control.

<http://scitation.aip.org/content/aip/proceeding/aipcp/10.1063/1.3251248>

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<http://plant149.factorbooks.com/>

SPIE | Proceeding | Overlay control using -

Metrology, Inspection, and Process Control Uwe Kramer; Michael Kubis; Anat Marchelli, et al. "Overlay control using scatterometry EUV Sources for Lithography" http://spiedigitallibrary.org/data/Conferences/SPIEP/21115/69222S_1.pdf

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<http://www.matespotter.com/search/Yiorgos-Raymond/>

Integrated scatterometry in high-volume -

Abstract: For several years, integrated scatterometry has held the promise of wafer-level process control. While integrated scatterometry on lithography systems is

http://www.academia.edu/4424515/Integrated_scatterometry_in_high-volume_manufacturing_for_polysilicon_gate_etch_control

SPIE | Volume -

Application of atomic force microscopy to lithography characterization and control. PDF. and Process Control for Microlithography XIII, 2 Yiorgos Kostoulas,

<http://proceedings.spiedigitallibrary.org/volume.aspx?volumeid=9273>

OSA | Scatterometry-based metrology with feature -

"Scatterometry-based metrology with feature region signatures matching "Novel implementations of scatterometry for lithography process control," in

<https://www.osapublishing.org/abstract.cfm?URI=oe-14-19-8482>

Robust lithography process control methodology -

Proceedings Paper Robust new methods to control and optimize lithography process by precisely after etching were measured by using a scatterometry

<http://spie.org/Publications/Proceedings/Paper/10.1117/12.598574>

In situ real time process characterization in -

In situ real time process characterization in nanoimprint lithography using time-resolved diffractive scatterometry NIL process control. 2004

http://www.princeton.edu/~chouweb/publications/167%20Yu_In%20situ%20real%20time%20nanoimprint_App%20Phys%20Lett_2004.pdf